Chip	Person	Date	Underlying Material	Cleaning Step	HMDS Prebake [temp (c), time (s)]	HMDS Spin Coat [RPM, time (s)]	HMDS Bake [temp (c), time (s)]	Photoresist Spin Coat [RPM, time (s)]	Photoresist Post Bake [temp (c), time (s)]	Exposure Patterns (Link to Digital Version)	Exposure Time (milliseconds)	Develop Time (s)	Metric: Pattern Quality Unit: Qualitative (-1, to 1) Tool: Microscope (light field images)	Photoresist leftover in exposed regions (1, 0) (1=yes, 0=no)	Photoresist missing in unexposed regions (1, 0) (1=yes, 0=no)	Metric: Contaminants on Chip Unit: Qualitative (-1 to 1) Tool: Microscope (light + dark field images)	Link to Metrology	Notes
207	Elio	10/2/2023	poly	acetone ipa	[100, 30]	[4000, 20]	[100, 40]	[4000, 30]	[100, 90]	Contact Resistan	4	75	0.8	1	0	0		4 exposures
208	Elio	10/2/2023	poly	acetone ipa	[100, 30]	[4000, 20]	[100, 40]	[4000, 30]	[100, 90]	Contact Resistan	4	85	0	1	0	0		3 exposures
209	Elio	10/2/2023	poly	acetone ipa	[100, 30]	[4000, 20]	[100, 40]	[4000, 30]	[100, 90]	Contact Resistan	4	85	0.8	1	0	0		3 exposures
206	Jay	11/2/2023	PolySi	Aceone + IPA	[100, 30]	[4000, 30]	[100, 20]	[4000, 30]	[100, 90]	https://docs.goog	4000	75	1	1	0	0		
210	Jay	11/2/2023	PolySi	Aceone + IPA	[100, 30]	[4000, 30]	[100, 20]	[4000, 30]	[100, 90]	https://docs.goog	4000	75	1	1	0	0		
211	Jay	11/2/2023	PolySi	Aceone + IPA	[100, 30]	[4000, 30]	[100, 20]	[4000, 30]	[100, 90]	https://docs.goog	4000	75	1	1	0	0		
202	Elio	9/27/2023	poly	acetone ipa	[100, 30]	[4000, 20]	[100, 40]	[4000, 30]	[100, 90]	transistors w con	4	85	0	1	0	0		
202	Elio	9/27/2023	700B	acetone ipa	[100, 30]	[4000, 20]	[100, 40]	[4000, 30]	[100, 90]	transistors w con	4	85	0	1	0	0		
175	Elio	10/10/2023	700B	acetone ipa	[100, 60]	[4000, 20]	[100, 60]	[4000, 30]	[100, 90]	transistors w con	4	75	0.5	0.8	0	0		
216					100,30	4000,30	100,20	4000,30	100,90		4000	80	1	-1	0			
306	Elio	1/29/2024	Polysilicon	Acetone, IPA	[100,60]	[4000,20]	[100,60]	[4000,30]			8000	70	1	0	0	0		
311																		